

PATENT ABSTRACTS OF JAPAN

(11)Publication number : 06-324474

(43)Date of publication of application : 25.11.1994

(51)Int.Cl.

G03F 1/08
G02F 1/136
H01L 21/027

(21)Application number : 05-132585

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(22)Date of filing : 10.05.1993

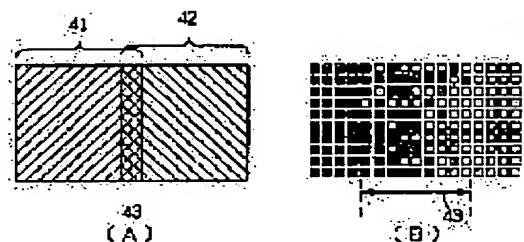
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(54) PHOTOMASK AND EXPOSING METHOD

(57)Abstract:

PURPOSE: To hardly perceive contrast difference caused on a connecting part in the case of performing exposure by picture synthesis.

CONSTITUTION: The connecting parts 43 obtained in the case of performing exposure by the picture synthesis are exposed to be overlapped to each other's, and unit patterns arrayed on the connecting part 43 are discretely, irregularly, and selectively exposed so that the unit patterns may not be repeatedly exposed twice or more. Thus, even through the contrast difference exists between the unit patterns formed on the connecting part, the unit patterns having the contrast difference are mixed, so that the connecting part is hardly perceived.



LEGAL STATUS

[Date of request for examination] 26.04.2000

[Date of sending the examiner's decision of rejection] 14.05.2002

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

[Date of requesting appeal against examiner's decision of rejection]

[Date of extinction of right]